# (12) UK Patent Application (19) GB (11) 2 237 887(13)A

(43) Date of A publication 15.05.1991

- (21) Application No 8923304.3
- (22) Date of filing 16.10.1989
- (71) Applicant Somar Corporation

(Incorporated in Japan)

11-2 Ginza 4-chome, Chuo-ku, Tokyo, Japan

- (72) inventors Osamu Ogitani Takashi Shimizu Ryuichi Fujii
- (74) Agent and/or Address for Service Lloyd Wise & Tregear & Co Norman House, 105-109 Strand, London, WC2R 0AE, United Kingdom

- (51) INT CL6 G03F 7/027
- (52) UK CL (Edition K) G2C CRM C1D3D C1GX C3V VBC C3W W125 W209 W225 W301
- (56) Documents cited None
- (58) Field of search UK CL (Edition J) G2C CRM CRPA CRPY INT CL4 G03C, G03F Online databases: Derwent WPI

#### (54) Photocurable composition

- (57) A photocurable composition useful for the preparation of printed wiring boards which includes
  - (a) 20-50 parts by weight of a modified rosin;
  - (b) 20-40 parts by weight of a first acrylic derivative expressed by the following formula:

HOOC-Y-COO-CH, CH, OCO-CCH, = CH,

wherein Y stands for 1,2-cyclohexylene;

- (c) 5-35 parts by weight of a second acrylic derivative selected from hydroxyalkyl acrylates and hydroxyalkyl methacrylates;
  - (d) 10-40 parts by weight of a monomer other than (b) and (c) and having one ethylenically unsaturated group;
  - (e) 0.5-15 parts by weight of a photopolymerization initiator; and
  - (f) 0.5-10 parts by weight of a montmorillonite organic complex.

The composition has good reproducibility and on exposure, the uncured areas are easily removable and the cured areas are resistant to chemicals such as etchants.

## PHOTOCURABLE, RESIST INK COMPOSITION

## Background of the Invention

This invention relates generally to a photocurable composition and, more specifically, to a resist ink useful in fabrication of printed wiring boards for forming, by screen printing, a wiring pattern which is curable by irradiation of UV rays and which becomes, upon curing, resistive against attack by chemicals such as an electroplating solution and an etching solution.

boards is known which includes the steps of screen printing of a resist ink on a board, curing of the printed ink by irradiation of UV rays, chemical etching with, for example, an aqueous ferric chloride or cupric chloride solution, and removing of the cured resin on the board using, for example, an aqueous caustic soda.

Another known method includes the steps of screen printing of a resist ink on a board, curing of the printed ink by irradiation of UV rays, electroplating with the use of, for example, cupric sulfate, and removing of the cured resin using, for example, an aqueous caustic soda.

The UV-curable resist ink to be used in the above methods should meet with the following criteria:

- (1) the ink should afford uniform wiring
  25 patterns with good reproducibility by screen printing;
  - (2) the cured ink should withstand chemical attack during the etching and electroplating steps; and
  - (3) the cured ink should be easily removable, generally by dissolution, during the removal step.
- Known resist inks are, however, not fully satisfactory in this regard.

2

### Brief Summary of the Invention

It is, therefore, the prime object of the present invention to provide a resist ink composition which satisfies all of the above conditions.

In accordance with the present invention there is provided a photocurable composition comprising the following ingredients (a)-(f):

- (a) 20-50% by weight of a modified rosin;
- (b) 20-40% by weight of a first acrylic
  10 derivative expressed by the following formula:

5

15

30

$$HOOC \longrightarrow COO-CH_2CH_2OCO-CCH_3=CH_2$$

- (c) 5-35% by weight of a second acrylic derivative selected from the group consisting of hydroxyalkyl acrylates and hydroxyalkyl methacrylates;
- (d) 10-40% by weight of a monomer other than said first and second acrylic derivatives and having one ethylenically unsaturated group;
- (e) 0.5-15% by weight of a photopolymerization 20 initiator; and
  - (f) 0.5-10% by weight of a montmorillonite organic complex.

Other objects, features and advantages of the present invention will become apparent from the detailed description of the invention to follow.

## Detailed Description of the Invention

Details of the ingredients (a)-(f) constituting the photocurable ink composition according to the present invention will be explained below.

The modified rosin to be used as the ingredient (a) is preferably one modified with an acid or an

alcohol, such as maleic acid, fumaric acid, maleic anhydride, pentaerythritol or glycerin. It is preferred that the modified rosin have an acid value of 70-300. When the acid value is lower than 70, it takes a 5 relatively long time to dissolve a cured layer of the resist ink composition in an aqueous alkali during the Too large an acid value of the modified removing step. rosin in excess of 300 tends to cause brittleness of the The modified rosin should be used in an cured layer. 10 amount of 20-50% by weight based on the total weight of the ingredients (a)-(f). An amount of the modified rosin below 20% by weight is disadvantageous because a long time is required for removing a cured layer of the resist ink composition by dissolution in an aqueous On the other hand, when the amount of the 15 alkali. modified rosin exceeds 50% by weight, the resulting composition becomes too viscous to print wiring patterns with good reproducibility.

The first acrylic derivative to be used as the ingredient (b) is monomethacryloyloxyethyl hexahydrophthalate (methacryloylethyl hydrogen hexahydrophthalate) of the formula:

This compound may be obtained by reaction of hexahydrophthalic anhydride with 2-hydroxyethyl methacrylate. The first acrylic derivative should be used in an amount of 20-40% by weight based on the total weight of the ingredients (a)-(f). When the amount of the first acrylic derivative is lower than 20% by weight, it takes a long time to dissolve a cured layer of the resist ink composition in an aqueous alkali during the

formula:

35

5 monoacryloyloxypropyl phthalate, monoacryloyloxyethyl tetrahydromethylphthalate of the formula:

monoacryloyloxypropyl tetrahydromethylphthalate, dicyclopentanyl acrylate of the formula:

dicyclopentenyl acrylate of the formula:

dicyclopentenyl acrylate modified with ethylene oxide of the formula:

isobornyl acrylate, monoacryloyloxyethyl phosphate, polycaprolactone monomethyacrylate, ethylene glycol

8 by weight, a cured layer of the resulting ink becomes so soft that it is easily injured. The montmorillonite organic complex to be used as the ingredient (f) is a montmorillonite having its 5 exchangeable cation ion-exchanged with an organic cation such as an alkyl ammonium or the formula  $(R^1)_nN(R^2)_m$ wherein R1 is hydrogen or a lower alkyl, R2 is a higher alkyl having 8-20 carbon atoms, n is an integer of 2 or 3, m is an integer providing m+n of 4. The lower alkyl 10 preferably has 1-3 carbon atoms and the higher alkyl preferably has 14-18 carbon atoms. A bentonite sol treated with dimethyl tallow alkyl ammonium chloride or trimethyl tallow alkyl ammonium chloride is particularly Such a montmorillonite organic complex preferably used. 15 may be commercially available as Esben (Hojun Yoko K. K.), New Olben (Shiraishi Kogyo K. K.) or Olben M The amount of the ingredient (Shiraishi Kogyo K. K.). (f) should be 0.5 to 10% by weight based on the total of the ingredients (a)-(f). An amount of the montmorillonite organic complex outside of the above 20 range fails to provide printed patterns with good reproducibility because of insufficient or excessive thixotropy of the resulting ink. Preferred amounts of the ingredients (a)-(f) 25 based on the total weight of the ingredients (a)-(f) are as follows: (a) 22-45% by weight; (b) 22-35% by weight; (c) 10-30% by weight; (d) 12-35% by weight; 30 (e) 1-10% by weight; and (f) 1-8% by weight. The photocurable ink composition of the present invention may contain a variety of conventional additives such as a polymerization inhibitor (e.g. methoquinone, BHT, kupferron), a pigment (e.g. Cyanin Blue, Carbon

Black, Cyanin Green), a filler (e.g. silica, barium sulfate, calcium carbonate, aluminum hydroxide, talc), a thixotropic agent (e.g. fine powder of anhydrous silica), an anti-foaming agent (e.g. silicone oil) or a surfactant (a nonionic surfactant).

The ink composition may be prepared in any known manner. For example, a mixture containing the ingredients (b), (c) and (d) is stirred by means of a dissolver at a temperature sufficient to melt the mixture, to which the ingredient (a) is added for dissolution therein. After the resulting mixture has been cooled to room temperature, the ingredient (e) is dissolved therein and, thereafter, the ingredient (f) is added. The mixture is homogeneously commingled by means of a three-roll mill, a ball mill or a sand mill to obtain the ink.

The following examples will further illustrate the present invention.

Examples 1 and 2 and Comparative Examples 1-3:

Resist inks having the compositions shown in Table 1 were prepared. In Table 1, the amounts are parts by weight. The performances of each of the inks were tested by the following methods and the results are

## 25 Pattern Reproducibility

summarized in Table 1.

Using each of the inks, screen printing is performed with 300 mesh Tetlon, an emulsion thickness of 6 µm and a line and space of 150 µm. The printed pattern is then placed on a belt conveyor and passed beneath two 80 W/cm high pressure UV lamps at a distance of 17 cm and a belt speed of 4 m/min, thereby to cure the pattern. The line width of the cured pattern is measured for the evaluation of the pattern

reproducibility. The pattern reproducibility is rated as follows:

good: the line width is in the range of 135-165  $\mu \mathrm{m}$ 

poor: the line width is outside of the 135-165  $\mu m$  range

## 5 Resistance to chemicals

Cured patterns are produced in the same manner as in the above test. The pattern is subjected to etching at 40°C for 60 seconds at a spray pressure of 1.5 kg/cm² using an aqueous cupric chloride solution as an etching solution. The line widths D<sub>0</sub> and D<sub>e</sub> before and after the etching, respectively, are measured to evaluate resistance to chemicals. The resistance is rated as follows:

good:  $D_e/D_0$  is 0.95 to 1.0

poor:  $D_e/D_0$  is below 0.95

#### Removability

15

Cured patterns are produced in the same manner as in the above tests. The pattern is immersed in a 3% by weight aqueous solution of sodium hydroxide and stirred at 40°C. The period of time required to dissolve the cured pattern is measured for the evaluation of the removability. The removability is rated as follows:

good: within 10 seconds

25 poor: more than 10 seconds

Iabie	_ -				
Example No.	Ex. 1	Ex. 2	Comp. 1	Comp. 2	Comp. 3
Ingredient (a)					
Maleic acid-modified rosin *1	0	35	35	0	0
Maleic acid-modified rosin *2	30	0	0	30	30
Ingredient (b) *3	30	20	15	30	30
Ingredient (c)					
2-Hydroxyethyl acrylate	10	20	40	10	10
Ingredient (d)					
Diethylene glycol monoethyl ether acrylate	22	0	0	10	22
Phenoxyethyl acrylate	0	15	0	0	0
Ingredient (e)					
2,4-Diethylthioxanthone	2	0	0	2	2
Isoamyl p-dimethylaminobenzoate	4	0	0	4	4
Benzoin isopropyl ether	0	S	S	0	0
Ingredient (f)					
Bentonite organic complex *4	2	2	2	2	0
Cyanine Blue	_	-	-	-	-
Calcium carbonate	20	0	0	20	30
Diethylene glycol diacrylate	0	0	0	12	0
Test Result					
Pattern reproducibility	goog	good	good	goog	poor
Resistance to chemicals	goog	goog	poor	good	goog
Removability	goog	good	goog	poor	poob
والمراجعة المراجعة المراجعة المراجعة والمراجعة					

÷

#### Remarks:

5

10

- \*1: Beccasite J-892, manufactured by Dainihon Ink Kagaku Kogyo K. K.
- \*2: Markeed 3002, manufactured by Arakawa Kagaku Kogyo K. K.
- \*3: Monoethacryloyloxyethyl hexahydrophthalate, manufactured by Mitsubishi Rayon K. K.
- \*4: Bentonite sol ion-exchanged with trimethyl tallow alkyl ammonium ion, Orben M, manufactured by Shiraishi Kogyo K. K.

#### Example 3:

Example 2 was repeated in the same manner as
described except that a mixture of 5 parts by weight of
benzoin isopropyl ether and 4 parts by weight of

2-hydroxy-2-propiophenone were used as the ingredient
(e). The cured pattern was found to exhibit better
adherence and a higher pencile hardness as compared with
that of Example 2. Further, the curing was able to be
completed with a higher belt speed than that in Example

20 2.

The invention may be embodied in other specific forms without departing from the spirit or essential characteristics thereof. The present embodiments are therefore to be considered in all respects as illustrative and not restrictive, the scope of the invention being indicated by the appended claims rather than by the foregoing description, and all the changes which come within the meaning and range of equivalency of the claims are therefore intended to be embraced therein.

#### CLAIMS:

٠.

- 1. A photocurable composition comprising the following ingredients (a)-(f):
  - (a) 20-50 parts by weight of a modified rosin;
- (b) 20-40 parts by weight of a first acrylic derivative expressed by the following formula:

HOOC 
$$\frac{}{\text{COO-CH}_2\text{CH}_2\text{OCO-CCH}_3\text{-CH}_3;}$$

- (c) 5-35 parts by weight of a second acrylic derivative selected from the group consisting of hydroxyalkyl acrylates and hydroxyalkyl methacrylates;
- (d) 10-40 parts by weight of a monomer other than said first and second acrylic derivatives and having one ethylenically unsaturated group;
- (e) 0.5-15 parts by weight of a photopolymerization initiator; and
- (f) 0.5-10 parts by weight of a montmorillonite organic complex.
- 2. A composition as claimed in Claim 1, wherein said modified rosin has an acid value of 70-300.
- 3. A composition as claimed in Claim 1, wherein said modified rosin is a rosin modified with an acid or an alcohol.
- 4. A composition as claimed in Claim 1, wherein said second acrylic derivative is a member selected from the group consisting of 2-hydroxyethyl acrylate, 2-hydroxyethyl methacrylate, 2-hydroxypropyl acrylate, 2-hydroxypropyl methacrylate and mixtures thereof.

A composition as claimed in Claim 1, wherein said monomer is a member selected from the group consisting of polycaprolactone monoacrylate, ethylene glycol monomethyl ether acrylate, ethylene glycol monoethyl ether acrylate, ethylene glycol monobutyl acrylate, diethylene glycol monomethyl ether acrylate, diethylene glycol monoethyl ether acrylate, diethylene glycol monobutyl ether acrylate, phenyl glycidyl ether acrylate, phenoxyethyl acrylate, phenoxypropyl acrylate, phenoxypolyethylene glycol acrylate, phenoxypolypropylene glycol acrylate, monoacryloyloxyethyl phthalate, monoacryloyloxypropyl phthalate, monoacryloyloxyethyl tetrahydromethylphthalate, monoacryloyloxypropyl tetrahydromethylphthalate, dicyclopentanyl acrylate, dicyclopentenyl acrylate, dicyclopentenyl acrylate modified with ethylene oxide, isobornyl acrylate, monoacryloyloxyethyl phosphate, polycaprolactone monomethyacrylate, ethylene glycol monomethyl ether methacrylate, ethylene glycol monoethyl ether methacrylate, ethylene glycol monobutyl methacrylate, diethylene glycol monomethyl ether methacrylate, diethylene glycol monoethyl ether methacrylate, diethylene glycol monobutyl ether methacrylate, phenyl glycidyl ether methacrylate, phenoxyethyl methacrylate, phenoxypropyl methacrylate, phenoxypolyethylene glycol methacrylate, phenoxypolypropylene glycol methacrylate, monomethacryloyloxyethyl phthalate, monomethacryloyloxypropyl phthalate, monomethacryloyloxyethyl tetrahydromethylphthalate, monomethacryloyloxypropyl tetrahydromethylphthalate, dicyclopentanyl methacrylate, dicyclopentenyl methacrylate, dicyclopentenyl methacrylate modified with ethylene oxide, isobornyl methacrylate, monomethacryloyloxyethyl phosphate and mixtures thereof.

. '

15

- 6. A composition as claimed in Claim 1, wherein said photopolymerization initiator is a member selected from the group consisting of benzoin alkyl ethers, acetophenone compounds, propiophenone compounds, anthraquinone compounds, thioxanthone, substituted thioxanthones, 1-hydroxycyclohexyl phenyl ketone and mixtures thereof.
- 7. A composition as claimed in Claim 1, wherein said photopolymerization initiator is a mixture of a benzoin compound of the following formula (I) with a priopiophenone compound of the following formula (II):

 $C_6H_5COCH(OR^1)C_6H_5$  (I)  $R^2-Z-COC(CH_3)_2OH$  (II)

wherein  $\mathbb{R}^1$  and  $\mathbb{R}^2$ , independently from each other, stand for hydrogen or an alkyl and Z stands for 1,4-phenylene.

- 8. A composition as claimed in Claim 7, wherein  $\mathbb{R}^1$  stands for hydrogen or an alkyl having 1-4 carbon atoms and  $\mathbb{R}^2$  stands for hydrogen or an alkyl having 1-12 carbon atoms.
- 9. A composition as claimed in Claim 8, wherein R<sup>1</sup> stands for hydrogen, methyl, ethyl, n-propyl, i-propyl or n-butyl and R<sup>2</sup> stands for hydrogen, methyl, ethyl, n-propyl, isopropyl or n-hexyl.
- 10. A composition as claimed in Claim 1, wherein the amount of the ingredients (a)-(f) are as follows:
  - (a) 22-45 parts by weight;
  - (b) 22-35 parts by weight;
  - (c) 10-30 parts by weight;
  - (d) 12-35 parts by weight;
  - (e) 1-10 parts by weight; and
  - (f) 1-8 parts by weight.

# This Page is inserted by IFW Indexing and Scanning Operations and is not part of the Official Record

## **BEST AVAILABLE IMAGES**

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images include but are not limited to the items checked:

<b>73</b> .	BLACK BORDERS
×	IMAGE CUT OFF AT TOP, BOTTOM OR SIDES
×	FADED TEXT OR DRAWING
	BLURED OR ILLEGIBLE TEXT OR DRAWING
	SKEWED/SLANTED IMAGES
×	COLORED OR BLACK AND WHITE PHOTOGRAPHS
	GRAY SCALE DOCUMENTS
	LINES OR MARKS ON ORIGINAL DOCUMENT
	REPERENCE(S) OR EXHIBIT(S) SUBMITTED ARE POOR QUALITY
	OTHER:

IMAGES ARE BEST AVAILABLE COPY.
As rescanning documents will not correct images problems checked, please do not report the problems to the IFW Image Problem Mailbox